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EP	A	6,566,147 B2	05/2003	Basceri et al.				
	AB	4,261,698	04/1981	Carr et al.				
	AC	4,691,662	09/1987	Roppel et al.				
	AD	5,270,241	12/1993	Dennison et al.	137	24	079	72
	Æ	5,312,783	05/1994	Takasaki et al.	4			
	AF.	5,392,189	02/1995	Fazan et al.				
	AG	5,395,771	03/1995	Nakato ·				
	AH	5,468,687	11/1995	Carl et al.				
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EF	2	0 030 798 A1	06/1981	EPO (Hughes Aircraft Company)			х	
EF	AK	GB 2 194 555 A	03/1988	UK (Nippon T & T Corporation)			X	
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W	Streiffer et al., Ferroelectricity in thin films: The dielectric response of fiber-textured (Ba _x Sr _{1-x})Ti _{1-y} O _{3+z} thin
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EP	*	5,614,018	03/1997	Azuma et al.			
	AB	5,656,329	08/1997	Hampden-Smith			
	AC.	5,663,089	09/1997	Tomozawa et al.			
	49	5,702,562	12/1997	Wakahara			
	Æ	5,719,417	02/1998	Roeder et al.	24	707	92
	AF	5,723,361	03/1998	Azuma et al.			
	AG	5,736,759	04/1998	Haushaalter			
EC	AH	5,525,156	06/1996	Manada et al.			
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EF	AJ	0 388 957 A2	09/1990	EPO (NEC Corporation)			х	
1	AK	08-060347	03/1996	Japan (Fujitsu Ltd)			X	
	₹	EP 0 810 666 A1	12/1997	EPO (Oki Electric)			x	
	AM	JP2000091333 _A	03/2000	Japan (Fujitsu Ltd)			X	
	AN	WO 01/16395 A1	03/2001	WIPO (Micron Technology)			х	
	AO	JP2250970	10/1990	Japan (NEC Corp.)	Υ		Abstract	
EP	2	04-024922	01/1992	Abstract:: Japan (Mitsubishi)			Abstract	

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EP	*	6,325,017 B1	12/2001	DeBoer et al.			
7	AB	5,976,990	11/1999	Mercaldi et al.			
	AC	5,989,927	11/1999	Yamonobe			
	AD	6,101,085	08/2000	Kawahara et al.			_ 0.0
	AE	6,215,650	04/2001	Gnade et al. E V 3	72	47U	142
	AF	6,258,654	07/2001	Gocho			
EF	AG	6,287,935 B1	09/2001	Coursey			
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EF	Al	EP 0 892 426 A2	01/1999	EPO (Ramtron International)			x	
	AJ	0 474 140 A1	30.08.91	EPO (Kamiyama)			х	
	AK	0 835 950 A1	13.10.97	EPO (Shinozaka et al.)	-		. х	
	AL.	04-115533	04/1992	Abstract: Japan (OKI Electric)			Abstract	
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tt		Chemical Vapor Deposition, 143 J. ELECTROCHEM Soc., No. 3, pp 977-983 (March 1996).
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	AB	5,006	6,363	04/1991	Fujii et al.					
	AC	5,164	4,363	11/1992	Eguchi et al.					
	Ð	5,183	3,510	02/1993	Kimura					
	Æ	5,254	4,505	10/1993	Kamiyama				-	
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	AG	5,459	9,635	10/1995	Tomozawa et al.					
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EF	AK	0 855	5 735 A2	07/1998	EPO (Applied Material	s)			:	
EF	AL	98/39	9497	09/1998	WIPO (Sec. of State for	r Defence/GB)				
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EF			Ultra-High	Density Dyna	mic Random Access Me	mories, Dept. of N	fat. Sci. &	Eng., NC	State Univ.	(1997).
100	AO		Cem Basceri e	t al., The diele	ctric response as a functi	on of temperature	and film	thickness o	of fiber-textu	red
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Form PTO-1449 U.S. DEPARTMENT OF COMMERCE ATTY. DOCKET NO. PRIORITY SERIAL PATENT AND TRADEMARK OFFICE MI22-2501 NO. 09/905,320 LIST OF ART CITED BY APPLICANT (Use several sheets if necessary) APPLICANT: Cem Basceri et al. **PRIORITY FILING DATE PRIORITY GROUP** July 13, 2001 ART UNIT 1762 **U.S. PATENT DOCUMENTS** Filing Date If Appropriate Date **Document Number** Class Subclass **Initials** Name 5,618,761 04/1997 Eguchi et al. AB 5,635,741 06/1997 Tsu et al. AC 5,711,816 01/1998 Kirlin et al. AD 5,731,948 03/1998 Yializis et al. Æ 07/1998 Yuuki et al. 5,776,254 5,783,253 07/1998 Roh 5,798,903 08/1998 Dhote et al. AH 5,834,060 11/1998 Kawahara et al. 5,909,043 06/1999 Summerfelt **FOREIGN PATENT DOCUMENTS** Document Number Subclass Date Country Class Yes A. 0 957 522 A2 11/1999 EPO (Matsushita Elec. Ind.) AK 99/64645 12/1999 WIPO (Applied Materials) AL OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) PRESENTATION: Steve Bilodeau et al., Composition Dependence of the Dielectric Properties of MOCVD BaxSr_{1-x}TiO₃, MRS Fall Meeting, Advanced Technology Materials (Dec. 1, 1994) pp. 1-21. Steve M. Bilodeau et al., MOCVD BST for High Density DRAM Applications, CVD Technologies for Inter-Level Dielectrics and Interconnects Symposium, SEMICON/WEST (July 12, 1995) 2 pages. ABSTRACT: Y. C. Choi et al., Improvements of the Properties of Chemical-Vapor-Deposited (Ba,Sr)TiO3 Films Through Use of a Seed Layer, JPN. J. APPL. PHYS., Vol. 1, Pt. 1, No. 11 (1997) pp. 6824-6828. **EXAMINER** DATE CONSIDERED 75 *EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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1	AB	6,14	i6,907	11/2000	Xiang et al.						
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EF			ULSI DRA	AM Application	s, Microelectronic Res. C	Center, Univ. of T	X at Austin	, TX (Unda	ted) 2 page	s.	
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